

**REMARKS**

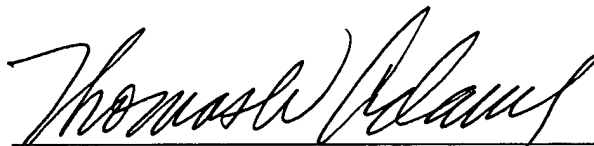
In the Office Action mailed September 17, 2002, the Examiner indicated that the stored charges 34a, 34b are shown in layer 28 instead of layer 30. This has been corrected herein. In addition, reference numerals 10 and 40 have been applied to the general structures shown in Figs. 1 and 2 respectively, and reference numeral 36 has been added to identify the silicon surface in Fig. 3.

An appropriately corrected formal drawing sheet including the requested correction is submitted herewith. A drawing sheet with the requested correction indicated in red ink is submitted for the Examiner's review with the Reply to Office Action which with this paper is filed. Appropriate consideration and entry of the corrected drawing sheet is respectfully requested.

If the Examiner considers that a telephone interview would be helpful to facilitate favorable prosecution of this application, the Examiner is invited to contact the undersigned at the telephone number below.

It is believed no fee is required for this filing. However, if a fee is required, please charge the fee to Deposit Account No. 18-0988, Order No. AF01120.

Respectfully submitted,  
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DATE: October 10, 2002

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